

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants :Sakae KOYATA et al. Group Art Unit : 1792
Appl. No. : 10/562,236 Examiner : Kin Chan Chen
Filed : February 7, 2007 Confirmation No. : 3799
For : MANUFACTURING METHOD OF SILICON WAFER

SECOND SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
U.S. Patent and Trademark Office
Customer Service Window, Mail Stop **AMENDMENT**
Randolph Building
401 Dulany Street
Alexandria, VA 22314

Sir:

In accordance with the duty of disclosure under 37 C.F.R. § 1.56 and §§ 1.97-1.98, and further to the Information Disclosure Statements filed December 24, 2008, and January 29, 2009, Applicants submit herewith a Japanese Office Action (and an English language translation of the same) mailed June 3, 2008, conducted in Japanese Patent Application No. 2003-401657, which is a counterpart of the above-captioned application. This document details the relevance of the following documents, as determined by the Japanese Examiner:

- 1) Japanese Patent Publication No. JP 2003-203890, Applications note that this document was previously made of record by the Information Disclosure Statement submitted January 29, 2009, and as such, no additional copy is provided herewith;
- 2) Japanese Patent Publication No. JP 2003-100701, Applications note that this document was previously made of record by the Information Disclosure Statement submitted December 24, 2008, and as such, no additional copy is provided herewith;

- 3) Japanese Patent Publication No. JP 11-171693, Applicants note that this document was previously made of record by the Information Disclosure Statement submitted December 24, 2008, and as such, no additional copy is provided herewith;
- 4) Japanese Patent Publication No. JP 2002-025950, published on January 25, 2002, and accompanied by an English language machine translation (Provided by Patent Abstracts of Japan);
- 5) Japanese Patent Publication No. JP 05-226203, published on September 3, 1993, and accompanied by an English language translation (provided by Patent Abstracts of Japan);

In order to complete the record, Applicants also provide herewith an English language translation of:

- 6) Korean Office Action, dated September 25, 2006, and corresponding to Korean Patent Application No. KR 10-2005-7024071, which is a counterpart of the above-captioned application. Applicants note that this Office Action was previously made of record by the Information Disclosure Statement submitted December 24, 2008; and
- 7) Chinese Office Action, dated August 10, 2007, and corresponding to Chinese Patent Application No. 200480018582.0, which is a counterpart of the above-captioned application. Applicants note that this Office Action was previously made of record by the Information Disclosure Statement submitted December 24, 2008.

Copies of the above-noted documents are enclosed together with a completed Form PTO-1449. The Examiner is accordingly requested to consider each of these documents, and to make them of record in this application by initialing in the appropriate spaces on the Form PTO-1449. Applicants respectfully request that the Examiner include a copy of the initialed Form PTO-1449 with the next communication from the U.S. Patent and Trademark Office.

The fee set forth in 37 C.F.R. § 1.17 (p) is paid by the attached check.

If there should be any questions, the Examiner is invited to contact the undersigned at the telephone number listed below.

Respectfully Submitted,
Sakae KOYATA et al.



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